

## Available Environmental Chamber Modifications for Semiconductor market

### Door Notch and Sliding Shelf

Applicable Series: Platinous J Series and AR Series

- Easy to install heavy objects
- Simplified wiring work

Specimen (a car navigation system, etc.)  
Slit  
Door notch  
Power supply, etc.

Rubber plug for door notch

**Door notch**  
Dimensions: H100 x D50 mm  
\* Including dedicated rubber plug

**Sliding shelf**  
Load capacity: Maximum load capacity 100kg  
Slide length: Approx. 700 mm

<https://espec.satori.site/products/catalog/usability#sec2>

### Slide Door

Applicable Series: Bench-Top Type Temperature (& Humidity) Chamber

- Simplified wiring work
- Sample demonstration available

Flat cable port type      Sample holder type

<https://espec.satori.site/products/catalog/usability#sec6>

### Rectangular Cable Port

Applicable Series: Thermal Shock Chamber TSA Series

- Simplified wiring for large connectors

Dimensions: H125 x D65 mm  
Max. number of ports: Maximum 2 on left side wall, Maximum 1 on right side wall

<https://espec.satori.site/products/catalog/usability#sec4>

### Removable Terminal Blocks      Sliding Panel-Mounted Terminal Blocks

Applicable Series: HAST Chamber

- Simple wiring + simple installation = reduced work time

Terminal block allows 12-pin specimen signal terminals in the test area to be inserted and removed at once

Terminal block that slides to the front

[https://www.espec.co.jp/products/book/hast/#target/page\\_no=13](https://www.espec.co.jp/products/book/hast/#target/page_no=13)

## Semiconductor Heat Treatment System

### Anaerobic Clean Oven (Oxygen concentration at 10 ppm)

Applicable Equipment: Anaerobic Clean Oven

- Ideal for low oxygen annealing required for 3D semiconductor packaging and integration.
- Supports heat treatment at oxygen concentrations as low as 10 ppm (0.001%) with Class 5 cleanliness
- Enables high-temperature annealing from 350 to 500 °C under low-oxygen conditions, with reduced process times through water cooling.

<https://espec.satori.site/products/catalog/highperformance#sec7>

## Large-Capacity Types

### Large Highly Accelerated Stress Test System—HAST Chamber      Rapid-Rate Thermal Cycle Chamber

Dimensions inside test area: Ø548 mm x L560 mm

<https://www.espec.co.jp/products/erv-test/ehs431/>

Internal dimensions (mm): W800 x H500 x D750

<https://www.espec.co.jp/products/catalog/tcc301.pdf>

## Power Semiconductor-Related Equipment

### High Temperature Reverse Bias Test System      Power Cycle Test System

Applicable Series: HTRB HTGB H3TRB AMI      RBS-PST

When the voltage of a power device is switched off, inductors in the circuit can generate surge voltages that may damage the device. Reverse bias testing is repeated to evaluate and improve product reliability.

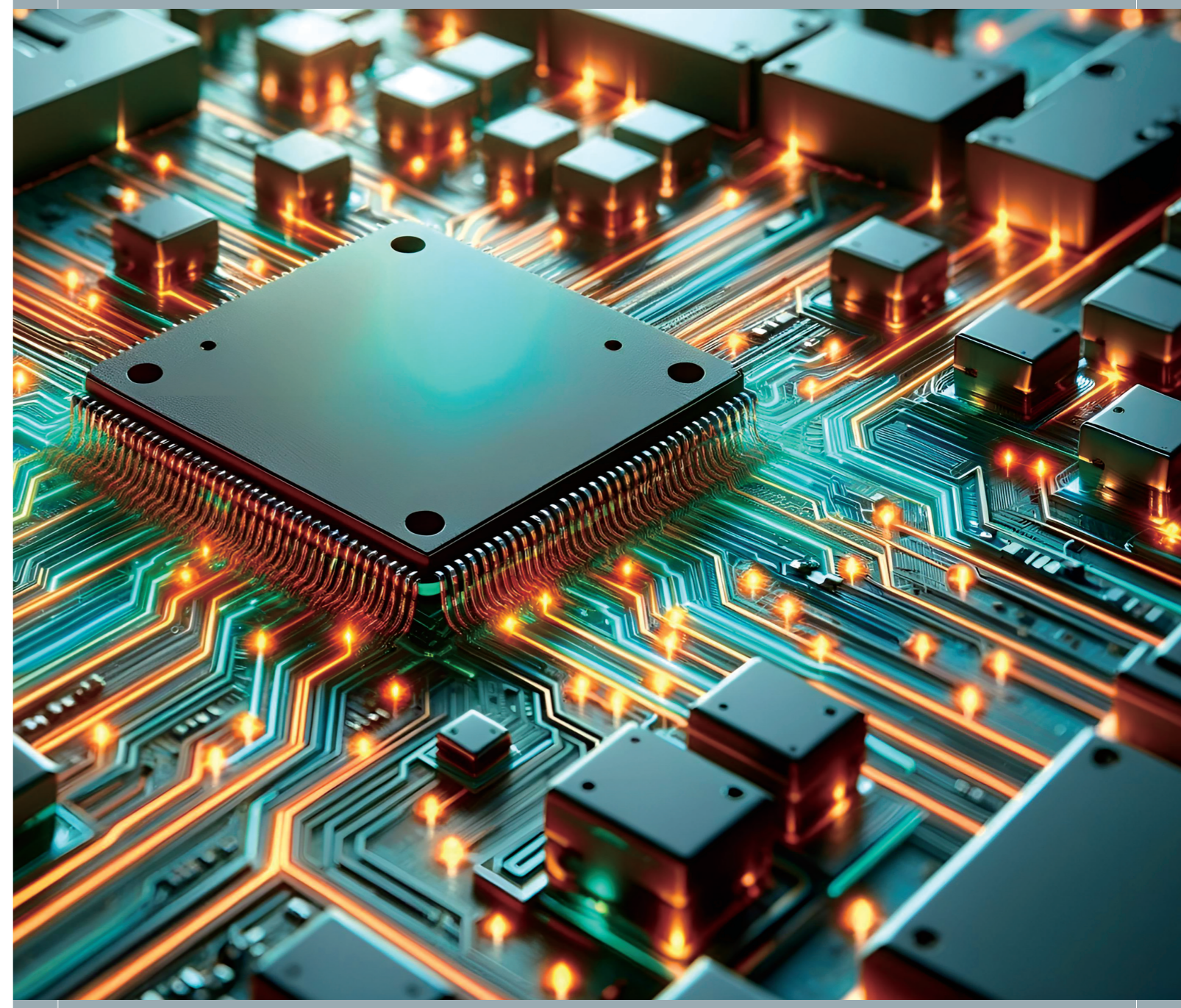
Drain power supply: 0 to 2 kV or 0 to 3 kV  
Gate power supply: 0 to ±30 V or 0 to ±35 V  
Temperature control: In-chamber DUT board connection type: 200°C or 350°C  
\* Temperature/humidity type is also available.

On/off current cycling in power devices causes self-heating, which can lead to wiring disconnections and damage to heat dissipation circuits. Power cycle testing evaluates these effects to improve product reliability.

**Major test modes**  
Continuous mode: Controls cooling water temperature and volume to maintain the device at the set temperature while "ice" remains constant.  
Vf cycle mode: Cycles "ice" on/off to achieve and maintain the target specimen temperature.  
Cycle mode: Cycles "ice" on/off at timed intervals

<https://www.espec.co.jp/products/measure-semicon/bias/>      <https://www.espec.co.jp/products/measure-semicon/fet-igt/>

## SEMICONDUCTOR RELATED EQUIPMENT



Thermal management is critical to the future of semiconductors.

# Semiconductor-Related Test Equipment/System Lineup

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As semiconductor performance and integration continue to advance, managing heat has become one of the most critical challenges. Effective thermal solutions are essential for enhancing performance, ensuring reliability, and extending device lifetimes. ESPEC offers a comprehensive lineup of systems designed with a focus on thermal management to support reliable heat control.

Process	Front-end process	Back-end process	Inspection	Reliability test field								
Technology trends	<b>Development of leading-edge processes of 2 nm level.</b> <ul style="list-style-type: none"> <li>EUV lithography</li> <li>Advanced deposition and lamination</li> <li>High-layer-count etching</li> <li>Micropattern (fine-pattern) cleaning</li> <li>Automated technology</li> </ul>	<b>Heterogeneous (chiplet) technology</b> <ul style="list-style-type: none"> <li>Leading-edge 2.xD and 3D packages</li> <li>Large interposers</li> <li>Chip stacking technology</li> <li>Fine redistribution layers</li> <li>Optoelectronic integration technology</li> <li>Low-dielectric materials</li> </ul>	<b>Screening during the process, final inspection</b> <ul style="list-style-type: none"> <li>Inspection methods for leading-edge processes such as the 2 nm node</li> <li>Inspection methods for chip stacking technologies</li> <li>Inspection methods for chiplet integration processes</li> </ul>	<b>Temperature and humidity test, thermal cycle test</b> <ul style="list-style-type: none"> <li>Compliant with reliability standards for leading-edge processes</li> <li>Enables reliable lifespan prediction for microscopic wiring processes</li> <li>Compliant with reliability standards for advanced 3D packages</li> <li>Enables reliable lifespan prediction for microscopic packaging technologies</li> </ul>	<b>Highly accelerated test (PCT)</b>	<b>Electrochemical migration evaluation of microscopic pattern insulation (HBT/HHBT)</b>	<b>Thermal cycle test, Rapid temperature change</b>	<b>Thermal shock test</b>	<b>Evaluation of microcracks in wire joints</b> <b>Reliability testing of microscopic wiring connections</b>	<b>HALT / HASS</b>	<b>Thermal management</b>	
	<b>Issues of leading-edge process operations, quality evaluation at the wafer level</b> <ul style="list-style-type: none"> <li>Reliability of chip bonding materials such as CoW</li> <li>Quality assurance methods in the front-end process</li> </ul>	<b>Quality evaluation in the middle-end and back-end process</b> <ul style="list-style-type: none"> <li>Fine redistribution layers and TSV interconnections</li> <li>Impact of local chip heat generation</li> <li>Quality of microscopic processes in the middle-end stage</li> </ul>	<b>Extraction rate improvement for leading-edge devices</b> <ul style="list-style-type: none"> <li>Process inspection in the front-end stage</li> <li>Process inspection in the middle-end stage</li> <li>Process inspection in the back-end stage</li> <li>Burn-in test for high-value semiconductors</li> </ul>	<b>Allowable high heat load, microscopic bonding technologies, and technologies to mount more pins</b> <ul style="list-style-type: none"> <li>Reliability of TSV joints</li> <li>Countermeasures for localized chip heat generation</li> <li>Board-level heat dissipation design</li> <li>Mitigation of thermal expansion between stacked materials</li> <li>Evaluation of multiple types of bonding materials</li> </ul> <p><b>Narrower bump pitches</b>  <b>Larger package sizes</b>  <b>Needs to mitigate warpage</b>  <b>Needs to develop low-thermal expansion materials and new bonding methods</b></p> <ul style="list-style-type: none"> <li>Compliance with semiconductor test standards</li> <li>JEITA ED4701/001A</li> <li>JEITA ED4701/100A</li> <li>Test method 102A: High-temperature, high-humidity bias test</li> <li>Test method 103A: High-temperature, high-humidity storage test</li> <li>Test method 104A: Humidification + Packaging stress series test</li> <li>Test method 105A: Thermal cycle test</li> <li>JEITA ED4701/200A</li> <li>Test method 201A: High-temperature storage test</li> <li>Test method 202A: Low-temperature storage test (reference test)</li> <li>Test method 203A: Temperature and humidity cycle test (reference test)</li> </ul>								
Our recommended products	<b>Wafer-level semiconductor characterization equipment</b> <ul style="list-style-type: none"> <li>Semiconductor Parametric test system (Wafer-Level) AMM Series</li> <li>TDDB Evaluation System (Wafer-Level) AMM Series</li> </ul>	<b>High-performance, Anaerobic Clean Oven</b> <ul style="list-style-type: none"> <li>SCO Series</li> <li>PVHC Series</li> </ul>	<b>Package level semiconductor characterization equipment</b> <ul style="list-style-type: none"> <li>Semiconductor Parametric test system (Package-Level) AMM Series</li> <li>TDDB Evaluation System SMU Type (Package-Level) AMM Series</li> </ul>	<b>Burn-in test-related equipment</b> <ul style="list-style-type: none"> <li>Static Burn-In System</li> <li>Dynamic Burn-In System</li> </ul>	<b>Temperature and humidity chambers</b> <ul style="list-style-type: none"> <li>Platinous Series</li> <li>AR Series</li> </ul>	<b>HAST chamber</b> <ul style="list-style-type: none"> <li>EHS Series</li> </ul>	<b>Semiconductor measurement systems</b> <ul style="list-style-type: none"> <li>Electrochemical Migration Evaluation System (AMI Series)</li> </ul>	<b>Rapid-rate thermal cycle chamber</b> <ul style="list-style-type: none"> <li>TCC Series</li> </ul>	<b>Thermal shock chamber</b> <ul style="list-style-type: none"> <li>TSA Series</li> <li>TSD Series</li> <li>TSB Series</li> </ul>	<b>Semiconductor measurement systems</b> <ul style="list-style-type: none"> <li>Conductor Resistance Evaluation System (AMR Series)</li> </ul>	<b>HALT / HASS</b> <ul style="list-style-type: none"> <li>T-Series</li> </ul>	<b>One-device, spot heating and cooling</b> <ul style="list-style-type: none"> <li>MTA Series</li> </ul>
	Defects in the front-end process can be evaluated at the wafer level using a combination of critical parameter tests, supported by a fully automated prober, to ensure reliability.	An ultra-low oxygen atmosphere enables the polyimide imidization at high temperatures (400 °C and above) while protecting devices from thermal degradation.  Heat treatment with precise temperature uniformity ensures the formation of consistent insulating films.	Semiconductor characteristics can be evaluated at the package level to assess the reliability impact of devices assembled or packaged during the back-end process.  Using a temperature chamber, transistor characteristics can also be measured in real time under controlled temperature conditions.	Burn-in testing is used to screen high-performance semiconductors such as SoCs and GPUs for potential defects. Devices are subjected to voltage loads or input signals at elevated temperatures to identify and eliminate failures before shipment.  This all-in-one system integrates burn-in functionality with a temperature chamber, providing a complete testing solution that has been widely adopted by customers.	Our chambers perform temperature and humidity testing in compliance with semiconductor reliability standards. A wide range of models are available, offering different capacities and environmental ranges to meet specific testing needs  Temperature and humidity chamber lineup <a href="https://www.espec.co.jp/products/catalog/temp_chamber_lineup.pdf">https://www.espec.co.jp/products/catalog/temp_chamber_lineup.pdf</a>	This series of dedicated PCT and HAST chambers accelerates deterioration in the form of failure mechanisms by applying pressure and humidity during semiconductor reliability testing.	This evaluation system provides real-time detection of insulation failures, such as electrochemical migration, in wiring patterns on RDLs and substrates.  When paired with a temperature and humidity chamber, its dedicated measurement circuits enable high-speed, high-accuracy capture of instantaneous insulation failures.	This chamber applies rapid temperature changes to specimens in full compliance with JEDEC standard testing and screening requirements.  It is ideal for evaluating automotive semiconductors, sensors, and other electronic devices.	Thermal shock chambers are designed for reliability testing by accelerating deterioration mechanisms, such as joint cracking, through rapid cycling between high and low temperatures. Both elevator-type and liquid-to-liquid configurations are available.	Microcracks in joints and other connection defects can lead to conduction failures under rapid temperature changes. When integrated with a thermal shock chamber, the conductor resistance evaluation system measures resistance in real time within a controlled temperature environment, enabling fast and accurate assessment of connection reliability.	This dedicated system evaluates electromigration in microscopic wiring. It supports accelerated testing at temperatures up to 450 °C.	Performing HALT (Highly Accelerated Life Testing) early in product development helps uncover design weaknesses, significantly improving reliability.  These systems also support HASS (Highly Accelerated Stress Screening) for production-level screening.
Standard	—	—	—	ED-4701/100A, 103A, IEC60068-2-1, IEC600682-2	IEC60068-2-66, ED-4701/100A, JESD22A118B	—	IEC60749-25, JESD22-A104F, ED-2531BNa	MIL-STD-883L, IEC60068-2-14Na, ED-2531BNa	—	—	—	—